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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: 1752

Serial No.: 10/629,806

Examiner: LEE, SIN J

Filed: July 30, 2003

Confirmation No.: 9494

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR  
FORMING RESIST PATTERN, AND PROCESS FOR MANUFACTURING  
SEMICONDUCTOR DEVICE**

Attorney Docket No.: 030923

Customer Number: 38834

**RESPONSE UNDER 37 CFR §1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

February 8, 2005

Sir:

This paper is in response to the Office Action dated November 29, 2004.

**Remarks** begin on page 2 of this paper.